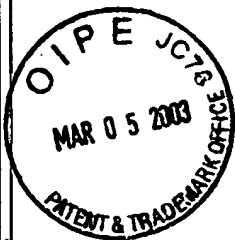


Attorney Docket
33082 M 083



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

CONFIRMATION NO. 1607

Applicants : Yutaka TAKAHASHI, et al.

Serial No. : 09/864,374

Art Unit : 1762

Filed : May 25, 2001

Examiner : Timothy H. MEEKS

For : Method for Forming Oxynitride Film or The Like
and System for Carrying Out The Same

#5
Meeke
3/10/03

RESPONSE TO PAPER NO. 4

Commissioner for Patents
Washington, DC 20231

Sir :

A response to the Office Action mailed February 12, 2003 is due by March 12, 2003.

The Action required restriction between the following five groups of claims:

- Group I of claims 1-3, drawn to an oxynitride deposition method;
- Group II of claims 4-7, 13-17, 21-25 and 28-31, drawn to a film deposition apparatus;
- Group III of claims 8-12, drawn to a silicon dioxide forming method with water formation;
- Group IV of claims 18-20, drawn to a silicon nitride deposition method; and
- Group V of claims 26-27, drawn to a silicon oxide deposition method with dinitrogen oxide gas.

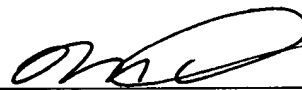
Applicants hereby elect Group II of claims 4-7, 13-17, 21-25 and 28-31, directed to a film deposition apparatus, for prosecution in this application. The election is made without traverse. No change is required in the inventorship of the application as a result of the election. Applicants reserve the right to file divisional application(s) for the non-elected claims in due course.

RECEIVED
MAR - 7 2003
TC 1700 MAIL ROOM

Applicants submit that this application now is in condition for examination on the merits and early action in that regard is solicited.

Respectfully submitted,

SMITH, GAMBRELL & RUSSELL, LLP



Michael A. Makuch, Reg. 32,263
1850 M Street, NW – Suite 800
Washington, DC 20036
Telephone : 202/263-4300
Facsimile : 202/263-4329

Date : March 5, 2003